

Figure 1: Lithographic contrast curve of select zinc-aluminum alkoxide films after 100 kV electron beam lithography and development in 0.2 M HCl. The addition of zinc dramatically increases lithographic contrast (the slope of the contrast curve), which correlates with pattern quality.

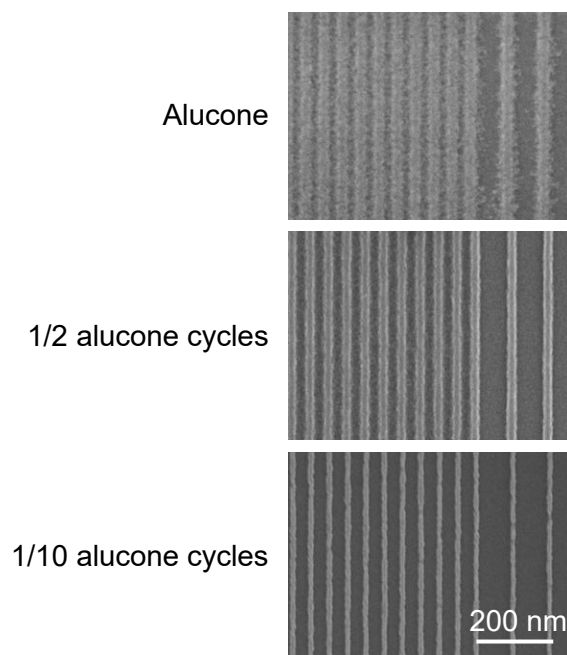


Figure 2: 1:1 line/space patterns at 24 nm half pitch at 170 mC/cm² electron dose and 0.2 M HCl development. Decreasing the fraction of alucone cycles results in less scumming, improving pattern quality.